L Number	Hits	Search Text	DB	Time stamp
-	51785	(mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:04
-	25136	((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:05
-	26	(((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4urethane adj3 $4acrylate or $4urethane adj3 $4acrylate)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:28
-	922	((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4acrylate or $4acrylate)) not ((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4urethane adj3 $4acrylate or $4urethane adj3 $4acrylate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:27
-	26	((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4urethane adj3 $4acrylate or $4urethane adj3 $4acrylate)) and (mask$3 or resist$3 or photoresist) same (peel$4 or pull$4 or remov$4 or lift$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32
-	854	(((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4acrylate or $4acrylate)) not ((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4urethane adj3 $4acrylate or $4urethane adj3 $4acrylate))) and (mask$3 or resist$3 or photoresist) same (peel$4 or pull$4 or remov$4 or lift$3 adj off)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:32

-	6	(((((mask$3 or resist$3 or photoresist) same ((etch$3 or chemical$2 adj mil$3 or deoxidiz$3 or anodiz$3) and metal)) and (mask$3 or resist$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask$3 or resist$3 or photoresist) same ($4urethane adj3 $4acrylate or $4urethane adj3 $4acrylate)) and (mask$3 or resist$3 or photoresist) same (peel$4 or pull$4 or remov$4 or lift$3 adj off)) and (mask$3 or resist$3 or photoresist) same (scrib$4 or cut$4 or mark$4 or scrap$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:34
-	1560	(mask$3 or resist$3 or photoresist) same ((deoxidiz$3 or anodiz$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:55
-	308	((mask$3 or resist$3 or photoresist) same ((deoxidiz$3 or anodiz$3) and metal)) and (peel$4 or remov$4 or scrib$4) adj3 (mask$3 or resist$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:10
-	495	((mask$3 or resist$3 or photoresist) same ((deoxidiz$3 or anodiz$3) and metal)) and (peel$4 or remov$4 or scrib$4 or pull$4 or lift$3 adj off) near3 (mask$3 or resist$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:11
-	511	((mask$3 or resist$3 or photoresist) same ((deoxidiz$3 or anodiz$3) and metal)) and (peel$4 or remov$4 or scrib$4 or pull$4 or lift$3 adj off or cut$4 or scrap$4) near3 (mask$3 or resist$3 or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:12
-	24	((mask$3 or resist$3 or photoresist) same ((deoxidiz$3 or anodiz$3) and metal)) and (peel$4 or remov$4 or scrib$4 or pull$4 or lift$3 adj off or cut$4 or scrap$4) near3 (mask$3 or resist$3 or photoresist) same (seal$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:19
-	1	(maskant or mask) and line adj sealant same ((deoxidiz$3 or anodiz$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:57
-	0	(maskant or mask) and line adj sealer same ((deoxidiz$3 or anodiz$3) and metal)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 10:29
-	92	(216/42,44,47,48,101-102 or 430/320,323-324 or 205/122,135,153,188,320,324).ccls. and seal$3 same mask$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 19:08
-	145	(IRGACURE adj "1700") or (IRACURE adj "1700")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/04 18:11
-	23	((IRGACURE adj "1700") or (IRACURE adj "1700")) and (wax or (synergist and triethanolamine))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/04 18:12